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P. J. em

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Inventor: KAICHIRO NAKANO, et al.
Serial No.: 09/036,219
Filed: March 6, 1998
Title: CHEMICALLY AMPLIFIED RESIST LARGE IN
TRANSPARENCY AND SENSITIVITY TO EXPOSURE LIGHT
LESS THAN 248 NANOMETER WAVELENGTH AND
PROCESS OF FORMING MASK
Examiner: J. CHU
Group Art Unit: 1752

May 21, 1999

Box Non-Fee Amendment
Assistant Commissioner for Patents
Washington, D. C. 20231

RECEIVED

MAY 27 1999

AMENDMENT

GROUP 1700

S I R :

Responsive to the Office Action dated April 27, 1999, please amend the
application as follows:

IN THE CLAIMS:

Please cancel claims 2, 4, 7 and 8 without prejudice.

REMARKS

In the outstanding Office Action restriction has been issued to elect the claims
between claims 1-8, drawn to resist composition, classified in claim 430, subclass 270.1
and claims 9-20, drawn to process of use, classified in class 430, subclass 325.

In addition an election requirement to elect a single species has been issued by the
Examiner.

Any fee due with this paper, not fully
covered by an enclosed check, may be
charged on Deposit Acct. No. 08-1634

Filed by Express Mail
(Receipt No. FM36676541B4S)
on 5-21-99
pursuant to 37 C.F.R.1.10.
by Frances Doyle